

Form PTO-1449 (MODIFIED)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 026827/0154	SERIAL NO. 09/658,023	
<p style="text-align: center;"><b>O P E</b> <b>INFORMATION DISCLOSURE CITATION</b> <b>FEB 20 2001</b> <i>(See several sheets if necessary)</i></p>				APPLICANT Boris KOBRIN, et al.		
				FILING DATE September 8, 2000	GROUP ART UNIT <i>1750 1763</i>	
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS
<i>Aero</i>	A1	4,751,170	06/14/1988	Mimura et al.	<i>      </i>	<i>      </i>
	A2	4,803,181	02/07/1989	Buchmann et al.	437	228
	A3	4,886,565	12/12/1989	Koshiba et al.	156	345
	A4	5,788,447	08/04/1998	Yonemitsu et al.	414	217
	A5	5,863,705	01/26/1999	Sezi et al.	430	311
	A6	6,100,014	08/08/2000	Lin et al.	430	314
<i>Aero</i>	A7	6,110,637	08/29/2000	Sezi et al.	430	270.1
FOREIGN PATENT DOCUMENTS						
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS
<i>Aero</i>	A8	JP 4-14049	01/20/1992	Japan	<i>      </i>	<i>      </i>
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
<i>Aero</i>	A9	"Nanometer Sidewall Lithography By Resist Silylation", P. Vettiger, et al., J. Vac. Sci. Technol., Nov./Dec 1989, Vol. 7, No. 6, pages 1756-1759				
EXAMINER <i>Aero</i>			DATE CONSIDERED <i>7/13/02</i>			
<p>* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.</p>						

Form PTO-1449  
(MODIFIED)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

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SERIAL NO.

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APPLICANT

Boris KOBRIN et al.

FILING DATE

09/08/2000

GROUP ART UNIT

1746 1763

OCT 24 2001

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PATENT &amp; TRADEMARK OFFICE

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
<i>Amo</i>	A1	4,657,845	4/14/87	Frechet et al.	430	326	
	A2	5,858,621	1/12/99	Yu et al.	430	313	
	A3	5,851,733	12/22/98	Sezi et al.	430	311	RECEIVED
	A4	4,377,437	3/22/83	Taylor et al.	156	2628	12-1PE 6 2001
	A5	4,377,734	3/22/83	Mashiko et al.	219	12-1PE 6 2001	
	A6	4,389,482	6/21/83	Bargon et al.	430	325	1700
	A7	4,419,809	12/13/83	Riseman et al.	029	570	
	A8	4,445,267	5/1/84	De La Moneda et al.	029	571	
	A9	4,502,914	3/5/85	Trumpp et al.	156	643	
	A10	4,504,574	3/12/85	Meyer et al.	430	331	
	A11	4,552,833	11/12/85	Ito et al.	430	325	
	A12	4,601,778	7/22/86	Robb	156	628	
	A13	4,613,398	9/23/86	Chiong et al.	156	628	
	A14	4,690,729	9/1/87	Douglas	156	643	
	A15	5,599,745	2/4/97	Reinberg	437	195	
	A16	5,792,593	8/11/98	McClure et al.	430	314	
	A17	5,825,609	10/20/98	Andricacos et al.	361	321.4	
	A18	5,665,251	9/9/97	Robertson et al.	216	022	
	A19	5,895,273	4/20/99	Burns et al.	438	719	
	A20	4,358,340	11/9/82	Fu	156	643	
	A21	4,209,349	6/24/80	Ho et al.	148	187	
<i>Amo</i>	A22	4,803,181	2/7/89	Buchmann et al.	437	228	

## FOREIGN PATENT DOCUMENTS

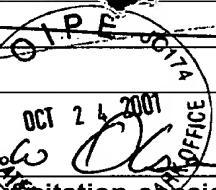
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION	
							YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>Amo</i>	B1	Wolf-Dieter Domle, "Chemical amplification of resist lines: The CARL process", Microlithography World, Spring 1999, pp. 2-5.
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*Allan W Ober* 7/13/02

EXAMINER	<i>[Signature]</i>	DATE CONSIDERED
		11/3/02
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